

Abstract:

Projection lens, in particular for microlithography  
(Figure 1)

5 A projection lens (3), in particular for microlithography, is  
provided with an object plane (7), with an image plane (9),  
with a lens arrangement (4) and with at least one gas chamber  
filled with gas or through which gas flows. The gas chamber is  
10 constructed as an approximately plane-parallel manipulation  
chamber (13). The refractive index can be varied in the  
manipulation chamber (13) by pressure changes and/or changes in  
gas composition.

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